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L1	32	(spatial with average) and (photosensitive with resist) and optical	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/22 14:08
L2	1	1 and alkaline	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/22 14:08
L3	2	1 and (dissolution with rate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/22 14:09
L4	359	alkaline with (dissolution adj rate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/22 14:09
L5	1	4 and (spatial with average)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/22 14:10
L6	6	4 and spatial	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/22 14:10
L7	8	("5379225" "5434440" "5745388").PN. OR ("5889686").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/11/22 14:35
L8	1732	((703/6) or (716/19,21)).CCLS.	USPAT	OR	OFF	2006/11/22 14:35
L9	52	8 and (photosensitive with resist)	USPAT	OR	OFF	2006/11/22 14:39
L10	1680	8 not 9	USPAT	OR	OFF	2006/11/22 14:39

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H Nakamura, Y Onishi, K Sato, S Tanaka, S Mimotogi ... - Journal of Microlithography, Microfabrication, and ..., 2005 - link.aip.org

... Nakae, A. Yamaguchi, K. Tsujita, and W. Wakamiya, "0.10 μ m dense hole pattern formation by double exposure utilizing alternating phase shift mask using KrF ...

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S. Büttgenbach

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- ☐ 1. **Laser scanning for semiconductor mask pattern generation**
 Allen, P.C.;
[Proceedings of the IEEE](#)
 Volume 90, Issue 10, Oct. 2002 Page(s):1653 - 1669
 Digital Object Identifier 10.1109/JPROC.2002.803664
[AbstractPlus](#) | [References](#) | Full Text: [PDF](#)(725 KB) | Full Text: [HTML](#) IEEE J
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- ☐ 2. **Energy distribution properties of focused ion beams from liquid metal ion**
 Uhm, H.S.; Choi, E.H.; Cho, G.S.; Kang, S.O.;
[Plasma Science, 1995. IEEE Conference Record - Abstracts., 1995 IEEE Inter Conference on](#)
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[High Energy Beam Processes for Industrial Applications. IEE Colloquium on](#)
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